# The 21st Korean Conference on Semiconductors
# 제21회 한국반도체학술대회
February 24–26, 2014 / Hanyang University, Seoul, Korea

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F. Silicon Device and Integration Technology 분과

## [WG2-F] Fin FETs, CIS and Power Devices

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| **Date** | Feb. 26, 2014 (Wed.) |
| **Place** | Room G / 제1공학관 405호 (# 405, Engineering Building I) |

Session Chair: 이종호 교수(서울대학교), 이병훈 교수(GIST)

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| **WG2-F-1** | **13:05-13:35** | **Performance Optimization Study of FinFETs Considering Parasitic Capacitance and Resistance**<br>저자: SoYoung Kim<br>소속: Department of Semiconductor Systems Engineering, Sungkyunkwan University |
| **WG2-F-2** | **13:35-13:50** | **Effect of Hydrogen Induced Gettering on Sensing Margin Enhancement of Si CMOS Image-Sensor Contaminated with Cu and Ni**<br>저자: Il-Hwan Kim, Seung-Hyun Song, Joo-Hyeong Park, Gon-Sub Lee, and Jea-Gun Park<br>소속: Department of Electronics and Communication Engineering, Hanyang University |
| **WG2-F-3** | **13:50-14:05** | **Optimization of 7V to 60V Low Vgs nLDMOS with Enhanced Specific On-Resistance**<br>저자: Min-Woo Kim, Cheol-Ho Cho, Choul-Joo Ko, Min-Seok Kim, Hyung-Gyun Jung, Hee-Bae Lee, Sun-Kyung Bang, Han-Geon Kim, Sung-Mo Gu, Sun-Kyoung Kang, and Jung-Ho Kang<br>소속: Product Integration Team, Dongbu Hitek |
| **WG2-F-4** | **14:05-14:20** | **Proposal of 90V Rated High-Side n-Type LDMOS Utilizing Double-Epi Process**<br>저자: Joowon Park, Kwangsik Ko, Soonyeol Park, Daehoon Kim, Jina Eum, Kuemju Lee, Sekyung Oh, Sanghyun Lee, Inwook Cho, and Kyungdong Yoo<br>소속: Technology Development team, SK hynix Inc. |